What Is Claimed Is:

1. A liquid crystal display panel, comprising:

a plurality of gate lines arranged along a first direction on a first substrate;

a plurality of data lines arranged along a second direction on the first substrate to cross the gate lines to define a plurality of unit pixels;

an insulating layer disposed over the gate and data lines;

a common electrode disposed on a second substrate opposite to the first substrate;

a plurality of pixel electrodes, each pixel electrode provided in each of the unit pixels partitioned by the gate line and the data line; and

a plurality of side electrodes overlapping the data lines,

wherein the insulating layer is provided between the side electrode and the data lines.

2. The panel according to claim 1, further comprising a thin film transistor provided in the unit pixel.

3. The panel according to claim 1, wherein the pixel electrode and the side electrode are made of a same material.

4. The panel according to claim 3, wherein the common electrode and the side electrodes comprise transparent conductive material films.

5. The panel according to claim 1, wherein each of the side electrodes are provided between adjacent unit pixels.

6. The panel according to claim 1, wherein the insulating layer includes an organic material film.

7. The panel according to claim 6, wherein the insulating layer includes at least one of benzocyclobutene (BCB), spin-on-glass (SOG), and photo-acryl.

8. The panel according to claim 1, wherein the side electrodes overlap the gate lines with at least the insulating layer therebetween.

9. The panel according to claim 1, wherein the pixel electrode is divided into a first region and a second region and the first and second regions are electrically interconnected by a connection region.

10. A liquid crystal display panel, comprising:

a plurality of gate lines formed on a first substrate;

a first insulating layer and an active layer formed on the first substrate;

a plurality of data lines formed on a surface of the active layer;

a second insulating layer formed on another surface of the active layer upon which the data lines are formed;

a plurality of side electrodes formed on a surface of the second insulating layer to overlap the data lines; and

a plurality of pixel electrodes formed on surfaces of the second insulating layer separated from the side electrodes.

11. The panel according to claim 10, wherein the first insulating layer is a gate insulating layer separating a gate electrode from the active layer.

12. The panel according to claim 10, wherein the second insulating layer includes an organic material layer.

13. The panel according to claim 10, further comprising:

a second substrate bonded to the first substrate;

a liquid crystal material layer formed between the first and second substrates;

a black matrix formed on a surface of the second substrate aligned to the gate lines and the data lines;

a color filter layer formed on the second substrate aligned with the unit pixel;

a common electrode formed on another surface of the second substrate upon which the black matrix and the color filter layer are formed; and

an electric field partition formed on the second substrate.

14. The panel according to claim 13, further comprising a liquid crystal material layer formed between the first and second substrates.

15. The panel according to claim 14, wherein the liquid crystal material layer has negative dielectric anisotropy.

16. The panel according to claim 13, wherein the electric field partition is a rib formed on a surface of the common electrode

17. The panel according to claim 13, wherein the electric field partition is a slit formed between adjacent portions of the common electrode.

18. The panel according to claim 10, further comprising a plurality of partitions formed on the first substrate between adjacent ones of the plurality of pixel electrodes.

19. A method for fabricating a liquid crystal display panel, comprising:

forming a plurality of gate lines, a plurality of data lines, and a plurality of thin film transistors on a first substrate;

forming a passivation layer on a surface of the first substrate upon which the gate lines, the data lines, and the thin film transistors are formed;

forming a transparent conductive material on a surface of the passivation layer;

forming a plurality of side electrodes overlapping the data lines by patterning the transparent conductive material;

forming a plurality of pixel electrodes separated from the side electrodes by patterning the transparent conductive material;

forming a black matrix, a color filter, and a common electrode on a second substrate;

forming an electric field partition on the common electrode;

bonding the first and second substrates together aligning the pixel electrodes to the common electrode; and

forming a liquid crystal material layer between the bonded first and second substrates.

20. The method according to claim 19, wherein the transparent conductive material includes at least one of indium tin oxide (ITO) an indium zinc oxide (IZO).

21. The method according to claim 19, further comprising etching the passivation layer to expose drain electrode portions of the thin film transistors.

22. The method according to claim 19, wherein the forming of an electric field partition includes forming at least one rib on a surface of the common electrode.

23. The method according to claim 19, wherein the forming of an electric field partition includes forming at least one slit in the common electrode by etching a part of the common electrode.

24. The method according to claim 19, wherein the forming a plurality of side electrodes and the forming a plurality of pixel electrodes is performed simultaneously by the patterning of the transparent conductive material.